IN THE CLAIMS:

Please CANCEL Claim 57 without prejudice to or disclaimer of the recited subject matter.

Please amend Claims 51, 53-55, 59 and 61 as follows.

1-50. (Canceled)

51. (Currently Amended) An exposure apparatus for exposing a wafer to ~~light~~ a pattern, said apparatus comprising:

a stage configured to hold the wafer and to move;

a scope having an image sensor and configured to obtain image data, ~~by accumulating~~ said image sensor being configured to store image signals corresponding to an image of a mark formed on said image sensor during an ~~accumulation~~ image storage period of said image sensor and to supply the stored image signals as the image data, the mark being held by said stage;

~~a stage position measurement system~~ a laser interferometer configured to measure a ~~position~~ deviation of said stage, ~~a plurality of times during the accumulation period of said image sensor~~ the deviation being a difference between a target position of said stage and an actual position of said stage; and

a controller configured to calculate an average ~~position~~ of ~~the~~ a plurality of ~~positions~~ the deviations of said stage measured by said laser interferometer during the ~~accumulation~~ image storage period, to calculate a position of the mark based on the image data obtained by said scope and data of the calculated average ~~position~~, and to control a position of said stage based on the calculated position of the mark.

52. (Previously Presented) An apparatus according to claim 51, wherein said image sensor is a CCD camera.

53. (Currently Amended) An apparatus according to claim 51, wherein said scope and said ~~stage position measurement system~~ laser interferometer are configured so that obtaining the image data by said scope and measuring the plurality of ~~positions~~ the deviations of said stage by said ~~stage position measurement system~~ laser interferometer are performed in sync with each other based on a sync signal.

54. (Currently Amended) An apparatus according to claim 51, wherein said scope is configured to send a sync signal to said ~~stage position measurement system~~ laser interferometer in accordance with the ~~accumulation~~ image storage period of said image sensor.

55. (Currently Amended) An apparatus according to claim 51, wherein said ~~stage position measurement system~~ laser interferometer is configured to ~~measure a position of said stage and to~~ send a sync signal to said scope based on the ~~measured position~~ deviation of said stage measured by said laser interferometer.

56. (Previously Presented) An apparatus according to claim 51, wherein said scope is an off-axis scope.

57. (Canceled)

58. (Previously Presented) An apparatus according to claim 51, wherein said scope is configured to obtain, as the image data, image data of a mark formed on the wafer.

59. (Currently Amended) An apparatus according to claim 51, wherein said controller is configured to cause said stage to move at a constant speed during the ~~accumulation~~ image storage period of said image sensor.

60. (Previously Presented) An apparatus according to claim 51, wherein said controller is configured to determine a mode to be applied to the calculation of the position of the mark.

61. (Currently Amended) A method of manufacturing a device, said method comprising steps of:

exposing a wafer to ~~light~~ a pattern using an exposure apparatus as defined in claim 51;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.